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Simulation and experimental study of gray-tone lithography for the fabrication of arbitrarily shaped ...

W Henke, W Hoppe, HJ Quenzer, P Staudt-Fischbach, ... - Proc. IEEE Int. Conf. on Micro Electro Mechanical Systems (...), 1994 - [ieeexplore.ieee.org](#)

... and the design of gray-tone masks was supported by II- thography **simulation**. ... here utilizes the fact that the projection system of the **wafer stepper** acts as a ...

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Statistical Circuit Simulation Modeling of CMOS VLSI

N Herr, JJ Barnes, II MOSFET - IEEE Transactions on Computer-Aided Design of Integrated ..., 1986 - [ieeexplore.ieee.org](#)
 ... drain field-effect, and channel length modulation terms in MOSFET **simulation** programs ...

to have a fully automatic mea- surement system and **wafer stepper** which can ...

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Design of due date assignment model and the determination of flow time control parameters for the ...

SH Chung, MH Yang, CM Cheng - IEEE TRANS COMPON PACKAG MANUF TECHNOL PART C, 1997 - [ieeexplore.ieee.org](#)

... **Wafer stepper** workstation (numbering 27) is defined as bottleneck resource ... cyclic material releasing sequence for all product types in each **simulation** run shall ...

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An Iterative Cutting Procedure for Determining the Optimal Wafer Exposure Pattern

II Procedure - IEEE TRANSACTIONS ON SEMICONDUCTOR MANUFACTURING, 1999 - [ieeexplore.ieee.org](#)

... study, the alignment machine is an ASM **wafer stepper**, and the ... neural networks, chemical vapor deposition, modeling and **simulation**, semiconductor manufacturing. ...

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Advanced simulation techniques for thick photoresist lithography

WW Flack, G Newman, DA Bernard, JC Rey, Y Granik, ... - Proceedings of SPIE, 1997 - [ultratech.com](#)

... 3.1 **Simulation** The first step in the **simulation** procedure is to properly describe the Ultratech 2244i **Wafer Stepper** lithography system. ...

[View as HTML](#) - [Web Search](#) - [adsabs.harvard.edu](#) - [link.aip.org](#)

The Significance and Detection of Transmissive Defects on 5X Reticles

LS Zurbrick, W Henke - Advanced Semiconductor Manufacturing Conference and Workshop ..., 1993 - [ieeexplore.ieee.org](#)

... system wavelengths and **wafer stepper** printing wavelengths ... defects on aerial image intensity profiles was studied using the UC Berkeley SPLAT' **simulation** software ...

[Web Search](#) - [ieeexplore.ieee.org](#)

A 10 GHz Digital Amplifier in an Ultra-Small-Spread High-J, Nb/Al-AlOx/Nbi Integrated Circuit ...

A Bhat, X Meng, S Whiteley, M Jeffery, T Van Duzer - IEEE TRANSACTIONS ON APPLIED SUPERCONDUCTIVITY, 1999 - [ieeexplore.ieee.org](#)

... Neither **simulation** nor detailed oscilloscope measurements revealed the effects of sympathetic switching ... the mask, and the use of a 10:1 **wafer stepper** to define ...

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Use of Short-Loop Electrical Measurements for Yield Improvement

I INTRODUCTION - IEEE TRANSACTIONS ON SEMICONDUCTOR MANUFACTURING, 1995 - [ieeexplore.ieee.org](#)

... The systematic variability from a **wafer stepper** has been extracted using a physically ...

5) TCAD **simulation** is performed on the detailed structures in order to ...

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Application of silicon-based process **simulation** tools to the fabrication of heterojunction bipolar ...
CH Fields, S Thomas - IEEE Transactions on Electron Devices, 2000 - ieeexplore.ieee.org
... of an in-situ tool for characterizing optical lithography **wafer stepper** systems. ...
for advanced III-V devices and circuits, process **simulation**, and high ...
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ZC Lin, WJ Wu - The International Journal of Advanced Manufacturing ..., 1998 - springerlink.com
... can be effec- tively improved. A multiple linear regression analysis of
a **simulation** study was carried out. The elimination of the ...
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IEE JNL IEE Journal or Magazine

IEEE CNF IEEE Conference Proceeding

IEE CNF IEE Conference Proceeding

IEEE STD IEEE Standard

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